

Title (en)
REACTIVE ION ETCHING PROCESS FOR ETCHING METALS

Title (de)
REAKTIVIONENÄTZVERFAHREN ZUM ÄTZEN VON METALLEN

Title (fr)
TRAITEMENT DE GRAVURE IONIQUE RÉACTIVE POUR GRAVER DES MÉTAUX

Publication
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Application
EP 07815243 A 20070926

Priority
AU 2007001425 W 20070926

Abstract (en)
[origin: WO2009039552A1] A method of etching a metal by a reactive ion etching process is provided. The etchant gas chemistry for the reactive ion etching process consists essentially of NH₃. The process is particularly suitable for etching superalloys, which etch only slowly using conventional metal etching techniques.

IPC 8 full level
C23F 1/12 (2006.01); **H01L 21/306** (2006.01); **H01L 21/3065** (2006.01)

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Citation (search report)
See references of WO 2009039552A1

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